

PATENT
1752-0165P

IN THE U.S. PATENT AND TRADEMARK OFFICE

Applicant: Toshitsura CHO et al. Conf.:
Appl. No.: NEW Group:
Filed: February 18, 2004 Examiner:
For: ABRASIVE SLURRY HAVING HIGH DISPERSION
STABILITY AND MANUFACTURING METHOD FOR A
SUBSTRATE

PRELIMINARY AMENDMENT

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

February 18, 2004

Sir:

The following preliminary amendments and remarks are respectfully submitted in connection with the above-identified application.

This amendment includes: Amendments to the Specification; Amendments to the Claims; and Remarks.